

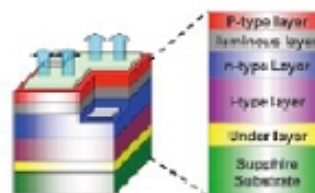
Explore vacuum technology to the future

# 真空技術で未来を拓く



**Semiconductor Sputtering**  
 DRAM<sup>※1</sup> wire / TiN Hard mask /  
 UBM<sup>※2</sup> / WLP<sup>※3</sup>

IC7200/7400/7500



**LED<sup>※6</sup>  
 Sputtering**



EC8100

**High Temp. Anneal for  
 SiC Power Device**

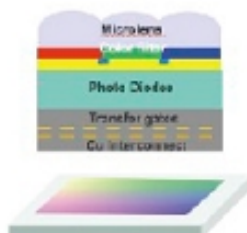


EC7200

**ReRAM / Metal Gate / CMOS-IS<sup>※4</sup>  
 Sputtering**



FC7100



**SAW<sup>※7</sup> filter  
 Sputtering**



EC7400

**MRAM<sup>※5</sup>  
 Sputtering**

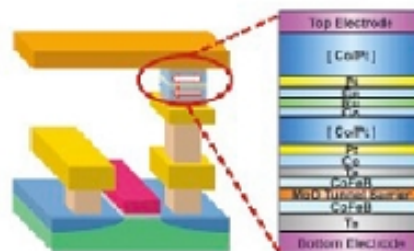


NC7900

**MRAM<sup>※5</sup>  
 Etching**



NC8000



EB1000



EB1000

**Sputtering for R&D /  
 Small-Scale Production**

※1 : Dynamic Random Access Memory, ※2 : Under Bump Metal, ※3 : Wafer Level Package, ※4 : Complementary Metal Oxide Semiconductor Image Sensor, ※5 : Magnetoresistive Random Access Memory, ※6 : Light Emitting Diode, ※7 : Surface Acoustic Wave,

# 原子再配列による常温拡散接合

Atomic Diffusion Bonding Equipment BC7000

## 原子拡散接合装置 BC7000

**加熱不要**

Without heating

**加圧不要**

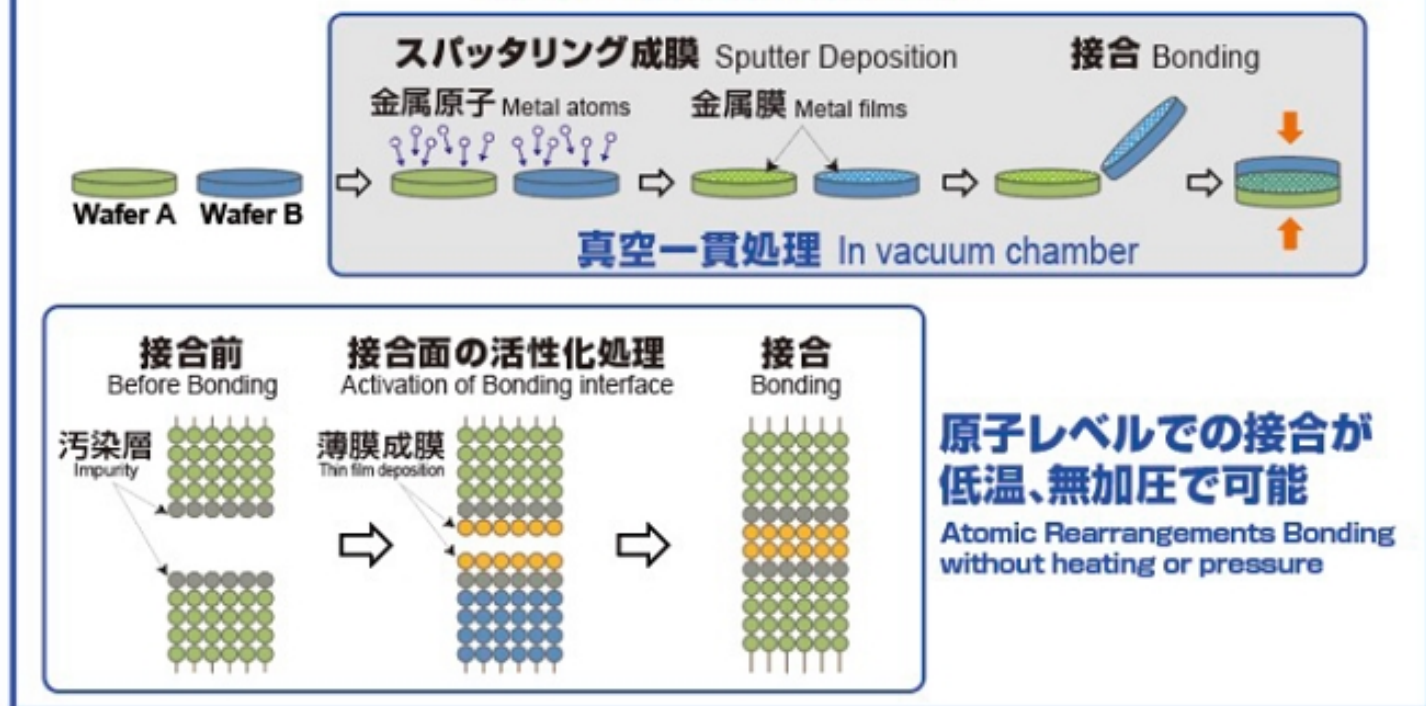
Without pressurising

**異種材料**

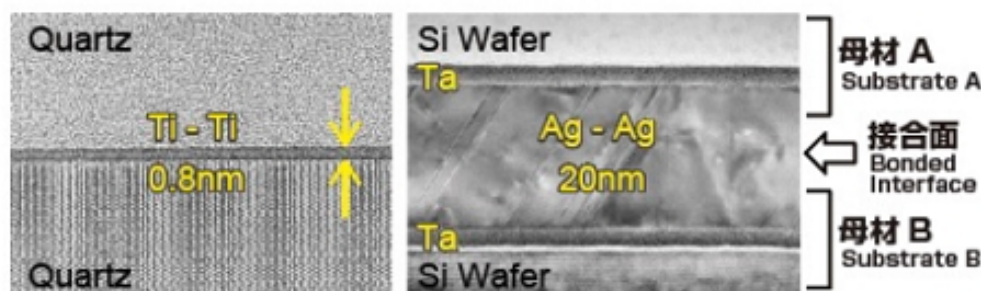
Different materials

### 真空一貫プロセス

In situ vacuum process



### 接合例 Example for bonding



Limited Sale  
BC 7000

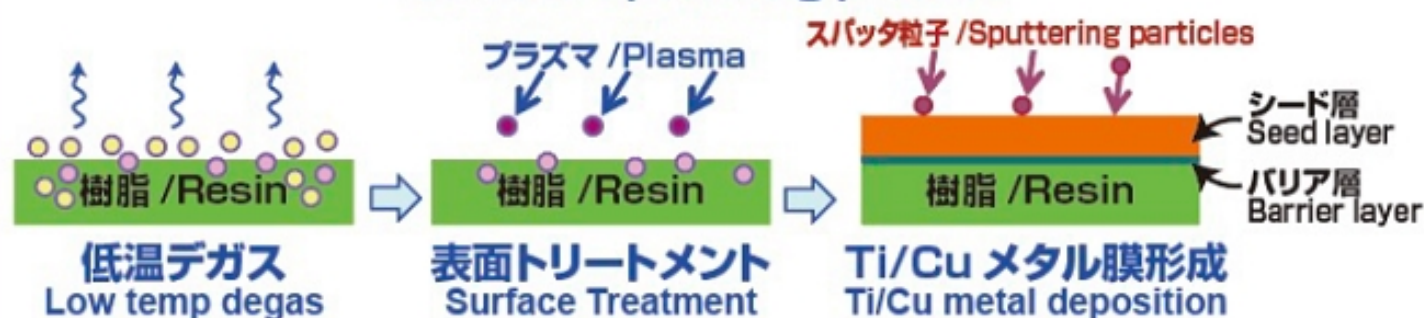
ご提供：東北大学 学際科学フロンティア研究所 島津研究室  
Courtesy of Frontier Research Institute for Interdisciplinary Sciences, Tohoku University, Shimatsu Labo.

Barrier · Seed metal formation on Large Package Panel  
大型実装パネルへのバリア・シードメタル形成

Packaging Sputter Equipment EL3400  
パッケージ向けスパッタリング装置 EL3400

銅メッキ下地膜形成

Cu seed Sputtering process



■ 大型基板スパッタ装置

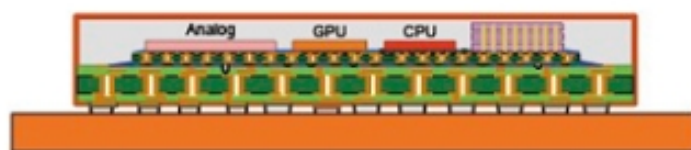
Large Board Sputter Equipment

■ 樹脂 / ガラス上への成膜

Deposition on Resin and Glass

■ 高密着性・高信頼性

High Adhesive and High Reliable



さまざまな実装プロセスのアプリケーション対応

New Solutions for Advanced Packaging



Limited Sale

EL3400

対応基板  
Substrates for EL3400

600mm PCB  
(MAX.650mm)

Multi-PCB  
(≤ 300 mm)